Applicants: Shoji Miyazaki et al.

Appl. No.: 10/809,217 Filed: March 25, 2004

page 7 of 9

REMARKS

Claims 45-65 are pending in the subject application. By this Amendment, Claim 45 has been amended. Applicants maintain that the amendments do not raise an issue of new matter. Support for amendment to Claim 45 can be found in the application at least on page 13, second to last paragraph, and page 44, top paragraph. Accordingly, entry of the amendment is respectfully requested.

Rejections under 35 U.S.C. §103(a)

Claims 45-48, 51, 55-60 and 62-65 are rejected as being unpatentable over Winarta et al. (U.S. Patent No. 6,287,451) ("Winarta") in view of Kawanaka et al. (U.S. Patent No. 6,599,406).

Claims 49, 53 and 54 are rejected as being unpatentable over Winarta et al. (U.S. Patent No. 6,287,451) ("Winarta") in view of Kawanaka et al. (U.S. Patent No. 6,599,406) and further in view of Ikeda et al. (U.S. Patent No. 5,582,697).

Claim 61 is rejected as being unpatentable over Winarta et al. (U.S. Patent No. 6,287,451) ("Winarta") in view of Kawanaka et al. (U.S. Patent No. 6,599,406) and further in view of Fujiwara et al. (U.S. Patent No. 6,004,441).

Applicants respectfully traverse these rejections.

Applicants also note that Claims 50 and 52 have not been included in the rejections.

Applicants note that in Winarta, the middle layer (30) in which cut-outs are formed is provided on the base insulating layer (20), and a reagent is provided in the opening of the cutouts, thereby regulating the position of the reagent. That is, the second type of slits which are positioned under the middle layer cannot contact the reagent; therefore, they cannot regulate the broadening (spreading) of the regent as in the present invention.

Applicants: Shoji Miyazaki et al.

Appl. No.: 10/809,217 Filed: March 25, 2004

page 8 of 9

In contrast, in the present invention, a second type of slits is provided such that the reagent is dripped on the electrode and the second type of slits regulates the broadening of the reagent by being in contact with the reagent. Thus, the present invention is characterized by being capable of controlling the position of the dripped reagent as well as its area. The second type of slits in Winarta is different in its constitution and function from the second type of slits in the present invention.

Applicants maintain that the cited references do not render the claimed invention obvious. Reconsideration and withdrawal of these rejections are respectfully requested.

<u>Supplemental Information Disclosure Statement</u>

This Supplemental Information Disclosure Statement (SIDS) is being submitted to make of record the Office Action issued on September 16, 2009 in co-pending patent family member U.S. Patent Application No. 13/322,684. All of the references cited in the Office Action are already of record in the subject application. The September 16, 2009 Office Action was issued less than three months prior to the filing of the present SIDS. Accordingly, this SIDS is being filed pursuant to 37 CFR 1.97(c)(1) and (e)(2). Applicants state that no item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the person signing the certification after making reasonable inquiry, no item of information contained in the information disclosure statement was known to any individual designated in § 1.56(c) more than three months prior to the filing of the information disclosure statement. Accordingly, no fee is deemed necessary in connection with filing this SIDS.

Applicants: Shoji Miyazaki et al.

Appl. No.: 10/809,217 Filed: March 25, 2004

page 9 of 9

CONCLUSIONS

In view of the amendments and remarks made hereinabove, reconsideration and withdrawal of the rejections in the July 24, 2009 Office Action and passage of the pending claims to allowance are respectfully requested. If there is any minor matter preventing the allowance of the subject application, the Examiner is requested to telephone the undersigned attorney.

The Patent Office is authorized to charge Deposit Account No. 01-1785 for the \$490.00 fee for a two month extension of time. No additional fee is deemed necessary in connection with the filing of this response. However, if any other fee is required to preserve the pendency of the subject application, authorization is hereby given to charge the amount of any such fee to Deposit Account No. 01-1785. Overpayments may also be credited to Deposit Account No. 01-1785.

Respectfully submitted,

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Dated: December 15, 2009

New York, New York

By /Alan D. Miller/

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